

259/079

09/925,884

LIST OF PATENTS AND OTHER ITEMS FOR APPLICANT'S
INFORMATION DISCLOSURE STATEMENT

APPLICANT:

Kenny, Michael et al.

FILING DATE:

August 6, 2001

GROUP:

(Use several sheets if necessary)

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE
ZE	AA 5,055,138	10/8/91	Slinn			
	AB 5,120,370	6/9/92	Mori et al.			
	AC 5,647,386	7/15/97	Kaiser			
	AD 5,181,985	1/26/93	Lampert et al.			
	AE 5,503,708	4/2/96	Koizumi et al.			
	AF 5,464,480	11/7/95	Mathews			
	AH 5,308,745	5/3/94	Schwartzkopf			
	AI 4,695,327	9/22/87	Grebinski			
	AJ 5,632,847	5/27/97	Ohno et al.			
	AK 5,911,837	6/15/99	Mathews			
	AL 5,705,089	1/6/98	Sugihara et al.			
	AM 5,244,000	9/14/93	Stanford et al.			
	AN 5,714,203	2/3/98	Schellenberger et al.			
	AO 5,896,875	4/27/99	Yoneda			
	AP 4,974,530	12/4/90	Lyon			
	AQ 5,248,380	9/28/93	Tanaka			
	AR 5,520,744	5/28/96	Fujikawa et al.			
	AS 5,415,191	5/16/95	Mashimo et al.			
	AT 5,658,615	8/19/97	Hasebe et al.			
	AU 5,858,107	1/12/99	Chao et al.			
	AV 5,235,995	8/17/93	Bergman et al.			
ZE	AW 5,378,317	1/3/95	Kashiwase et al.			

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ZE	AX	5,971,368	10/26/99	Nelson et al.			
	AY	5,234,540	8/10/93	Grant et al.			
	AZ	5,803,982	9/8/98	Kosofsky et al.			
	BA	5,944,907	8/31/99	Ohmi			
	BB	5,232,511	8/3/93	Bergman			
	BC	5,776,296	7/7/98	Matthews			
	BD	5,071,485	12/10/91	Matthews et al.			
	BE	4,778,532	10/18/88	McConnell et al.			
	BF	4,899,767	1/13/90	McConnell et al.			
	BG	5,964,954	10/12/99	Matsukawa et al.			
	BI	5,032,218	7/16/91	Dobson			
	BI	6,249,933	6/2001	Bergman			
	BJ	6,267,125	7/2001	Bergman et al.			
	BK	6,273,108	8/2001	Bergman et al.			
	BL	5,950,643	9/1999	Miyazaki et al.			
	BM	6,146,469	11/2000	Toshima			
	BN	4,917,123	4/90	McConnell et al.			
	BO	5,105,556	4/92	Kurokawa et al.			
	BP	5,326,406	7/94	Kaneko et al.			
	BQ	4,186,032	1/80	Ham			
	BR	4,749,440	6/88	Blackwood et al.			
	BS	4,817,652	4/89	Liu			
	BT	5,832,177	11/98	Shinagawa et al.			
ZE	BU	5,964,952	10/99	Kunze-Concewitz			

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ZE	BW	5,503,708	4/96	Korizumi et al.			
	BX	5,378,317	1/95	Kashiwase et al.			
ZE	BY	5,571,367	11/96	Nakajima et al.			

FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION YES NO
ZE	BZ	0 548 596 A2	6/3/93	Europe			
	CA	0 344 764	12/6/89	Europe			
	CB	0 702 399	3/20/96	Europe			
	CC	GB 2 287 827	9/27/95	United Kingdom			
	CD	JP52-12063		Japan			
	CE	JPO 4 301 145		Japan			
	CF	EP 587 889		EPO			
	CG	JP 401042129		Japan			
	CH	WO 99/52654	10/21/99	PCT			
ZE	CI	WO 01/07177 A1	2/1/01	PCT			

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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

ZE	CJ	Abstract of JP 3041729 published 2/22/91
	CK	Abstract of JP 1008630, published 1/12/89
	CL	Abstract of Japanese Appln. No. 63-16127 published July 31, 1989.
	CM	Abstract of Japanese Appln. No. 52-100473 published March 14, 1979.
	CN	Abstract of Japanese Appln. No. 1-192712 published March 12, 1992.
ZE	CO	Translation/Abstract of Japanese Appln. No. 1984-125760 published January 10, 1986.

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ZE	CP	Heyns, M.M., et al. "New Wet Cleaning Strategies for Obtaining Highly Reliable Thin Oxides," MRP Symposium Proceedings on Materials Research Society, Spring Meeting, San Francisco, CA April 13-15, 1993, p. 35 (1993)
	CQ	Adler, Marilyn Grace and Hall, George Richard, "The Kinetics and Mechanism of Hydroxide Ion Catalyzed Ozone Decomposition in Aqueous Solution" <i>J. Am. Chem. Soc.</i> , Volume 72, pp. 1884-86, 1950.
	CR	Nelson, Steve, "Ozonated water for photoresist removal" <i>Solid State Technology</i> , pp. 107-112 (July 1999)
	CS	Christenson, Kurt K., et al. "Deionized Water Helps Remove Wafer Stripping 'Resist'-ance," <i>www.precisioncleaningweb.com - Precision Cleaning Web - Archives</i> , pp. 10-20 (April 1998)
	CT	Sehested, K., et al., "Decomposition of Ozone in Aqueous Acid Solutions (pH 0-4)," <i>J. Phys. Chem.</i> , pp. 1005-1009 (1992)
	CU	Krusell, W.C. et al., "Cleaning Technology for High Volume Production of Silicon Wafers," <i>ECS Proc. of the First Int'l. Symposium on Cleaning Technology I Semiconductor Device Mfg.</i> , pp. 23-32 (October 1989)
	CV	Vig, John R., "UV/Ozone Cleaning of Surfaces," <i>U.S. Army Elec. Tech. and Devices Lab.</i> , pp. 1-26
	CW	Vig, John R., "UV/Ozone Cleaning of Surfaces: A Review," <i>Surface Contamination: Genesis, Detection, and Control</i> , pp. 235-253(1979)
	CX	Tong, Jeremy, et al., "Aqueous Ozone Cleaning of Silicon Wafers," <i>ECS Extended Abstracts, Phoenix, AZ</i> , Abstract No. 506, pp. 753 (October 13-17, 1991)
	CY	Zafonte, Leo, et al., "UV/Ozone Cleaning For Organics Removal on Silicon Wafers," <i>SPIE Optical Microlithography III: Technology for the Next Decade</i> , Vol. 470, pp. 164-175 (1984)
	CZ	Baumgärtner, H., et al., "Ozone Cleaning of the Si-SiO ₂ System," <i>Appl. Phys. A</i> , Vol. 43, pp. 223-226 (1987)
	DA	Isagawa, Tatsuhiko, et al., "Ultra Clean Surface Preparation Using Ozonized Ultrapure Water," <i>Extended Abstracts of the 1982 Int'l. Conf. on Solid State Devices and Materials</i> , pp. 193-195 (1992)
	DB	Shimada, H., et al., "Residual-Surfactant-Free Photoresist Development Process," <i>J. Electrochem. Soc.</i> , 139(6):1721-1730 (June 1992)
	DC	Tong, Jeremy K. et al., "Aqueous Ozone Cleaning of Silicon Wafers," <i>Proc. of 2nd Int'l. Symposium on Cleaning Tech. In Semiconductor Device Mfg.</i> , pp. 18-25 (October 1992)
	DD	Tong, Jeremy K., et al., "Aqueous Ozone Cleaning of Silicon Wafers," <i>Res. Soc. Symp.</i> , pp. 18-25 (1993)
	DE	Ohmi, T., et al., "Native Oxide Growth and Organic Impurity Removal on Si Surface with Ozone-Injected Ultrapure Water," <i>J. Electrochem. Soc.</i> , 140(3):804-810 (March 1993)
	DF	Vig, John R., et al., "UV/Ozone Cleaning of Surfaces," <i>IEEE Transactions on Parts, Hybrids, and Packaging</i> , Vol. PHP-12(4):365-370 (December 1976)
	DG	Vig, John R., "UV/ozone cleaning of surfaces," <i>U.S. Army Electronics Technology and Devices Laboratory, ERADCOM, Ft. Monmouth, NJ, 07703-5302</i> , pp. 1027-1034 (September/October 1984)
	DH	Tabe, Michiharu, "UV ozone cleaning of silicon substrates in silicon molecular beam epitaxy," <i>Appl. Phys. Lett.</i> , 45(10):1073-1075 (November 1984)
	DI	Zazzera, L.A., et al., "XPS and SIMS Study of Anhydrous HF and UV/Ozone-Modified Silicon (100) Surfaces," <i>J. Electrochem. Soc.</i> , 136(2):484-491 (February 1989)
	DJ	Gabriel, Calvin, et al., "Reduced Device Damage Using An Ozone Based Photoresist Removal Process," <i>SPIE Advances in Resist Technology and Processing VI</i> , Vol. 1086, pp. 598-604 (1989)
ZE	DK	Suemitsu, Maki, et al., "Low Temperature Silicon Surface Cleaning by HF Etching/Ultraviolet Ozone Cleaning (HF/UVOC) Method (I) -Optimization of the HF Treatment-", <i>Japanese Journal of Applied Physics</i> , 28(12):2421-2424 (December 1989)

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ZE	DL	Kern, Werner, "The Evolution of Silicon Wafer Cleaning Technology," <i>J. Electrochem. Soc.</i> , 137(6):1887-1892 (June 1990)
	DM	Kasi, S.R., et al., "Surface Hydrocarbon Removal from Si by UV/Ozone," <i>ECS Extended Abstracts</i> , No. 458, pp. 691-692 (199)
	DN	Kasi, Srinandan R., et al., "Vapor phase hydrocarbon removal for Si processing," <i>Appl. Phys. Lett.</i> , 57(20):2095-2097 (November 1990)
	DO	Huynh, Cuc K., et al., "Plasma versus ozone photoresist ashing: Temperature effects on process-induced mobile contamination," <i>J. Vac. Sci. Technol.</i> , B9(2):353-356 (Mar/Apr 1991)
	DP	Bedge, Satish, et al., "Kinetics of UV/O ₂ Cleaning and Surface Passivation Experiments and Modeling," <i>Mat. Res. Soc. Symp. Proc.</i> , Vol. 259, pp. 207-212 (1992)
	DQ	Goulding, M.R., "The selective epitaxial growth of silicon," <i>Materials Science and Engineering</i> , Vol. B17, pp. 47-67 (1993)
	DR	Ganesan, Gans S., et al., "Characterizing Organic Contamination in IC Package Assembly," <i>The Int'l. Soc. for Hybrid Microelectronics</i> , Vol. 17, #2, Second Quarter, pp. 152-160 (1994)
	DS	Egitto, F.D., et al., "Removal of Poly(Dimethylsiloxane) Contamination From Silicon Surfaces With UV/Ozone Treatment," <i>Mat. Res. Soc. Symp. Proc.</i> , Vol. 385, pp. 245-250 (1995)
	DT	Amick, J.A., "Cleanliness and the Cleaning of Silicon Wafers," <i>Solid State Technology</i> , pp. 47-52 (November 1976)
	DU	Bolon, D.A., et al., "Ultraviolet Depolymerization of Photoresist Polymers," <i>Polymer Engineering and Science</i> , 12(2):108-111 (March 1972)
	DV	Krusell, W.C., et al., "The Characterization of Silicon Substrate Cleaning Treatments by use of SIMS and MOS Electrical Testing," <i>ECS Extended Abstracts</i> , No. 229, p. 331-332 (1986)
	DW	Golland, D.E., et al., "The Clean Module: Advanced Technology for Processing Silicon Wafers," <i>Semiconductor Int'l.</i> , pp. 184-187 (September 1987)
	DX	Anantharaman, Ven, Ph.D., et al., "ORGANICS: Detection and Characterization of Organics in Semiconductor DI Water Processes," <i>Ultrapure Water</i> , pp. 30-36 (April 1994)
	DY	"Ozone Concentration Measurement In A Process Gas," <i>Proposed IOA Pan American Group Guideline</i> , pp. 1-21 (December 1993)
ZE	DZ	"Ozone for Semiconductor Applications," <i>Sorbios</i> , pp. 1-6 (October 1991)

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